

Dr. Mike Cooke



Dr Mike Cooke is Plasma Technology's CTO, and has worked on plasma etching and deposition processes and tool developments for more than 35 years. He was responsible for the development of 'cryogenic etching' at OIPT, several plasma and ion sources, and plasma enhanced atomic layer etching and deposition tools. He has led and participated in several joint development projects, including three projects scaling plasma etch and deposition tools for processing 450mm silicon. In 2016 he was appointed 'OI Fellow', one of six across Oxford Instruments.